

# INTERFERENCE

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| L18   | 0    | ((test same pattern same wafer) and configur\$4 and adjust\$4 and (layout or laid adj out) and (region or area) and sensitive and fabricat\$4).CLM. | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | ON      | 2005/10/16 12:23 |


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Display Format: ☒ Citation ☐ Citation & Abstract

IEEE JNL IEEE Journal or Magazine

IEEE JNL IEE Journal or Magazine

IEEE CNF IEEE Conference Proceeding

IEEE CNF IEE Conference Proceeding

IEEE STD IEEE Standard

Select Article Information

- ☐ **1. Sensor for monitoring the rinsing of patterned wafers**  
 Jun Yan; Seif, D.; Raghavan, S.; Vermeire, B.; Barnaby, H.J.; Peterson, T.; Sh  
 Semiconductor Manufacturing, IEEE Transactions on  
 Volume 17, Issue 4, Nov. 2004 Page(s):531 - 537  
 Digital Object Identifier 10.1109/TSM.2004.837001  
[AbstractPlus](#) | [References](#) | Full Text: [PDF](#)(1144 KB) IEEE JNL
- ☐ **2. Large deflection micromechanical scanning mirrors for linear scans and generation**  
 Schenk, H.; Durr, P.; Haase, T.; Kunze, D.; Sobe, U.; Lakner, H.; Kuck, H.;  
 Selected Topics in Quantum Electronics, IEEE Journal of  
 Volume 6, Issue 5, Sept.-Oct. 2000 Page(s):715 - 722  
 Digital Object Identifier 10.1109/2944.892609  
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| L1    | 322  | (test same pattern same fabricat\$4 same wafer) and configur\$4                       | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | ON      | 2005/10/16 10:45 |
| L2    | 88   | (test same pattern same fabricat\$4 same wafer) and configur\$4 and layout and device | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | ON      | 2005/10/16 10:45 |
| L3    | 5    | (test same pattern same fabricat\$4 same wafer same configur\$4) and layout           | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | ON      | 2005/10/16 10:45 |
| L4    | 58   | (pattern same fabricat\$4 same wafer same configur\$4) and correla\$4                 | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | ON      | 2005/10/16 10:45 |
| L5    | 3    | ((test near4 pattern) same fabricat\$4 same configur\$4) and correla\$4               | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | ON      | 2005/10/16 10:45 |
| L6    | 27   | ((test near4 pattern) same configur\$4) and correla\$4 and fabricat\$4 and layout     | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | ON      | 2005/10/16 10:45 |
| L7    | 249  | ((test near4 pattern) same configur\$4) and correla\$4                                | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | ON      | 2005/10/16 11:42 |
| L8    | 118  | ((test near4 pattern) same configur\$4) and adjust\$4 and (layout or laid adj out)    | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | ON      | 2005/10/16 11:43 |

|     |     |                                                                                                                                                   |                                                                   |    |    |                  |
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| L9  | 97  | ((test near4 pattern) same configur\$4) and adjust\$4 and (layout or laid adj out) and (region or area)                                           | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2005/10/16 11:44 |
| L10 | 8   | ((test near4 pattern) same configur\$4) and adjust\$4 and (layout or laid adj out) and (region or area) and "716"/\$.ccls.                        | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2005/10/16 11:44 |
| L11 | 5   | ((test near4 pattern) same configur\$4) and adjust\$4 and (layout or laid adj out) and (region or area) and fabricat\$4 and "716"/\$.ccls.        | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2005/10/16 12:05 |
| L12 | 16  | (test same pattern same wafer) and configur\$4 and adjust\$4 and (layout or laid adj out) and (region or area) and fabricat\$4 and "716"/\$.ccls. | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2005/10/16 12:06 |
| L13 | 222 | (test same pattern same wafer) and configur\$4 and adjust\$4 and (layout or laid adj out) and (region or area) and fabricat\$4                    | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2005/10/16 12:20 |
| L14 | 28  | (test same pattern same wafer) and configur\$4 and (adjust\$4 same (layout or laid adj out)) and (region or area) and fabricat\$4                 | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2005/10/16 12:08 |
| L16 | 7   | ((test same pattern same wafer) and configur\$4 and adjust\$4 and (layout or laid adj out) and (region or area) and fabricat\$4).CLM.             | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2005/10/16 12:22 |
| L19 | 149 | (test same pattern same wafer) and configur\$4 and adjust\$4 and (layout or laid adj out) and (region or area) and sensitive and fabricat\$4      | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2005/10/16 12:24 |

|     |   |                                                                                                                                                                             |                                                                   |    |    |                  |
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| L20 | 7 | (test same pattern same wafer)<br>and configur\$4 and adjust\$4 and<br>(layout or laid adj out) and (region<br>or area) and sensitive and<br>fabricat\$4 and "716"/\$.ccls. | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2005/10/16 12:25 |
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